

	Hits	Search Text	DBs
11	15	((low\$3k or dielectric or silicon\$5nitride or SiON or (low\$4 near16 dielectric)) same (upper\$3 or surface or top or convert\$4) same (sacrific\$4 or cap\$2 or SiO\$2 or (silicon near5 \$3oxide)) same (plasma\$4 near9 (ash\$5 or treat\$6 or oxidation or oxidiz\$5))) and ((low\$3k or dielectric or silicon\$5nitride or SiON or (low\$4 near16 dielectric)) same (heat\$9 or bak\$4 or anneal\$4)) and ((pattern\$6 or photolithograph\$8 or lithograph\$6) same (via or trench or dual\$9damascene)) and via and trench and ((out\$5gas\$5 or dissipat\$4 or eliminat\$4 or rid\$4 or dispos\$4 or exhaust\$4) same (volatile or contaminat\$4 or poison\$4) same (substrate or dielectric or low\$3k or wafer))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
12	6	((low\$3k or dielectric or silicon\$5nitride or SiON or (low\$4 near16 dielectric)) same (upper\$3 or surface or top or convert\$4) same (sacrific\$4 or cap\$2 or SiO\$2 or (silicon near5 \$3oxide)) same (plasma\$4 near9 (ash\$5 or treat\$6 or oxidation or oxidi\$5))) and ((low\$3k or dielectric or silicon\$5nitride or SiON or (low\$4 near16 dielectric) or SSQ or silsesquioxane) near22 (heat\$9 or bak\$4 or anneal\$4 or cur\$3) near40 (eliminat\$4 or dissipat\$5 or reduc\$4 or (drive near2 off) or (rid\$4)) near19 (contaminant\$4 or water or poison\$6 or volatil\$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
13	266	((low\$3k or dielectric or silicon\$5nitride or SiON or (low\$4 near16 dielectric) or SSQ or silsesquioxane) near22 (heat\$9 or bak\$4 or anneal\$4 or cur\$3) near40 (eliminat\$4 or dissipat\$5 or reduc\$4 or (drive near2 off) or (rid\$4)) near19 (contaminant\$4 or water or poison\$6 or volatil\$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
14	93	((low\$3k or dielectric or silicon\$5nitride or SiON or (low\$4 near16 dielectric) or SSQ or silsesquioxane) near4 (layer or film or coating) near22 (heat\$9 or bak\$4 or anneal\$4 or cur\$3) near40 (eliminat\$4 or dissipat\$5 or reduc\$4 or (drive near2 off) or (rid\$4)) near19 (contaminant\$4 or water or poison\$6 or volatil\$5))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB